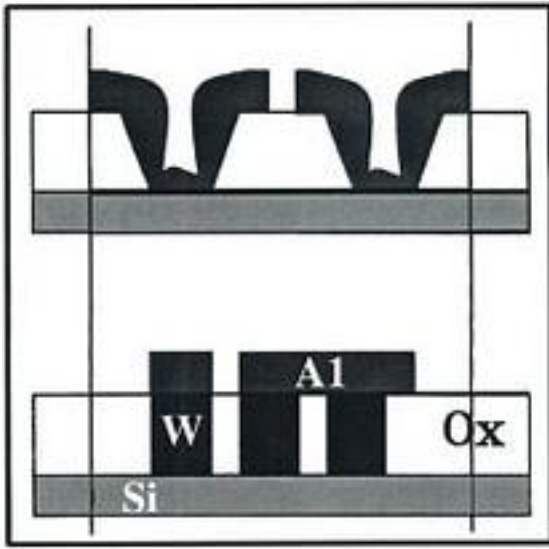


Chemical Vapor Deposition of Tungsten and Tungsten Silicides for VLSI/ ULSI Applications

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CHEMICAL VAPOR DEPOSITION OF TUNGSTEN AND TUNGSTEN SILICIDES For VLSI/ULSI Applications



by
John E. J. Schmitz

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著者:Schmitz, John E. J.

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This monograph condenses the relevant and pertinent literature on blanket and selective CVD of tungsten (W) into a single manageable volume. The book supplies the reader with the necessary background to bring up, fine tune, and successfully maintain a CVD-W process in a production set-up. Materials deposition chemistry, equipment, process technology, developments, and applications are described.

作者介绍:

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